

**Amendments to the Claims:**

The listing of claims will replace all prior versions, and listings, of claims in this application:

**Listing of Claims:**

Claim 1 (previously amended): For use in a plasma reactor including a plasma reactor chamber, a workpiece support for holding a workpiece inside said chamber during processing and an inductive antenna, an article comprising:

a window electrode proximal a wall of said chamber, said antenna and wall being positioned adjacently, said window electrode being operable as:

(a) a capacitive electrode accepting RF power to capacitively couple plasma source power into the chamber, and

(b) a window electrode passing RF power therethrough from said antenna into said chamber to inductively couple plasma source power into the chamber.

Claim 2 (original): The article of Claim 1 wherein said window electrode comprises a semiconductor electrode.

Claim 3 (original): The article of Claim 1 further comprising an RF plasma source power supply connected to said window electrode to produce a capacitively coupled plasma.

Claim 4 (original): The article of Claim 3 wherein said RF plasma source power supply is connected across said workpiece support and said window electrode.

Claim 5 (original): The article of Claim 1 further comprising an RF plasma source power supply connected to said antenna to produce an inductively coupled plasma.

Claim 6 (original): The article of Claim 5, further comprising a bias RF power supply coupled to said window electrode.

Claim 7 (original): The article of Claim 6 wherein said bias RF power supply is connected across said support and said window electrode.

Claim 8 (original): The article of Claim 7 wherein said window electrode operates simultaneously as a window to the inductive antenna, and as a counter electrode to said support.

Claim 9 (original): The article of Claim 1 wherein said window electrode comprises a portion of said wall.

Claim 10 (canceled)

Claim 11 (original): The article of Claim 1 wherein said window electrode comprises a sidewall portion of said reactor enclosure generally perpendicular to and surrounding a periphery of said support.

Claim 12 (original): The article of Claim 11 wherein said inductive antenna is adjacent said sidewall portion.

Claim 13 (currently amended): A plasma reactor comprising:  
a plasma reactor chamber;  
a workpiece support for holding a workpiece inside said chamber during processing  
a window electrode ~~facing~~ above said support;  
an inductive source power applicator external of said chamber and ~~facing~~ adjacent said window electrode;  
wherein said reactor further comprises one of:  
(a) an RF plasma source power supply connected to said window electrode to capacitively couple RF plasma source power into said chamber,  
(b) an RF plasma source power supply connected to said inductive source power applicator to inductively couple RF plasma source power through said window electrode into said chamber.

Claim 14 (original): The reactor of Claim 13 wherein said reactor further comprises in combination with the RF power supply connected to the inductive power applicator an RF bias power source coupled to said window electrode.

Claim 15 (original): The reactor of Claim 14 wherein said bias RF power source is connected across said support and said window electrode.

Claim 16 (original): The reactor of Claim 15 wherein said window electrode operates simultaneously as a window to the inductive applicator, and as a counter electrode to said support.

Claim 17 (original): The reactor of Claim 13 wherein said window electrode comprises a semiconductor electrode.

Claim 18 (original): The reactor of Claim 17 wherein said semiconductor electrode comprises silicon.

Claims 19-27 (canceled)